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- (71) Applicant (for all designated States except US): **INTENSE LIMITED** [GB/GB]; 4 Stanley Boulevard, Hamilton International Technology Park, High Blantyre, Glasgow G72 0BN (GB).
- (72) Inventors; and
- (75) Inventors/Applicants (for US only): **YANSON, Dan, Andreyevitch** [RU/GB]; 52 Springhill Gardens, Glasgow

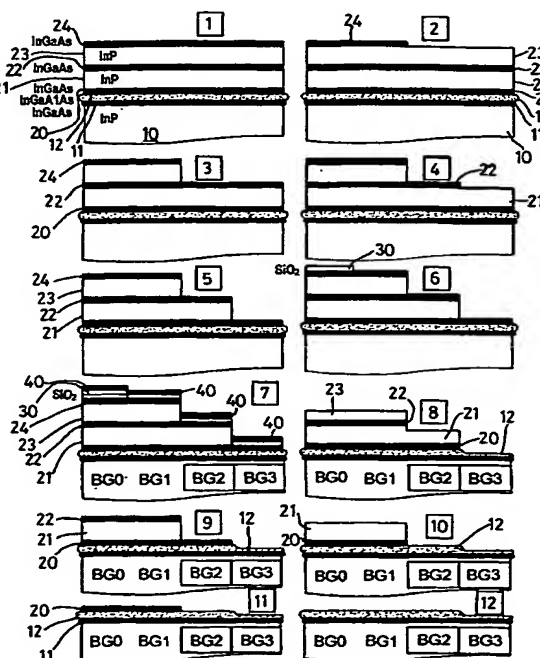
G41 2EY (GB). **BACCHIN, Gianluca** [IT/GB]; Flat 14, 260 Camphill Avenue, Glasgow G41 3AS (GB). **KOWALSKI, Olek, Peter** [GB/GB]; 2 Tylney Road, Paisley PA1 3JN (GB). **MCDUGALL, Stewart, Duncan** [GB/GB]; 1 Hazelbank Braes, Hazelbank, Lanark ML11 9XL (GB).

(74) Agent: **CHARIG, Raymond**; Eric Potter Clarkson, Park View House, 58 The Ropewalk, Nottingham NG1 5DD (GB).

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(54) Title: GENERATING MULTIPLE BANDGAPS USING MULTIPLE EPITAXIAL LAYERS



(57) Abstract: A quantum well intermixing (QWI) technique for modifying an energy bandgap during the formation of optical semiconductor devices enables spatial control of the QWI process so as to achieve differing bandgap shifts across a wafer, device or substrate surface. The method includes: forming a substrate comprising one or more core layers defining at least one quantum well; depositing a succession of intermixing barrier layers over the quantum well, each successive intermixing barrier layer being formed of a semiconductor material and having a different etch characteristic than an immediately preceding barrier layer; etching away different numbers of the successive barrier layers in different regions of the substrate so as to provide different total thicknesses of barrier layer in different regions of the substrate; and applying an intermixing agent to the surface of the substrate such that the degree of intermixing in the quantum well region varies as a function of the total thickness of barrier layer, thereby forming different bandgaps in the quantum well in each of the respective regions.



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